## Notice of References Cited Application/Control No. | Applicant(s)/Patent Under Reexamination GUILLERMO ET AL. | Examiner | Art Unit | Page 1 of 1

## **U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	Α	US-6,687,010	02-2004	Horii et al.	356/479
	В	US-			
	С	US			
	D	US-		·	
	Е	US-		·	
	F	US-			
	G	US-			
	Н	US-			
	1	US-			
	J	US-			
	K	US-			
	L	US-			
	. М	US-			

## FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	WO 99/44089	09-1999		General Hospital Corporat	G02B 21/00 ·
	: o					
	P					
	Q			•		
	: R					
	s					
	T					

## **NON-PATENT DOCUMENTS**

* Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)						
	U	Erdelyi et al. "Generation of diffraction-=free beams for applications in optical microlithography", J. Vac. Sci. Technol. B 15 (2), Mar/Apr 1997, pp. 287-292.				
	v					
	w					
	x					

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)

Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.